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1752

PATENT  
30205/37456

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Geun Su Lee et al.	)	I hereby certify that this paper and the
	)	documents referred to as enclosed
Serial No.: 09/884,313	)	therewith are being deposited with the
	)	United States Postal Service as first class
Filed: June 19, 2001	)	mail, postage prepaid, on August 7, 2003,
	)	in an envelope addressed to
For: Photoresist Polymer for Top-	)	Commissioner for Patents, P.O. Box
Surface Imaging Process by Silylation	)	1450, Alexandria, Virginia 22313-1450
and Photoresist Composition	)	
Containing the Same	)	
	)	
Group Art Unit: 1752	)	Michael R. Hull
	)	Reg. No. 35,902
Examiner: Yvette C. Thornton	)	Attorney for Applicants

1752

AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In response to the office action mailed on May 19, 2003, please amend the  
above-identified patent application as follows: